

Docket No.: 0171-1079PUS1  
(PATENT)

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

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In re Patent Application of:  
Hiroki YOSHIKAWA et al.

Application No.: 10/811,924

Confirmation No.: 3156

Filed: March 30, 2004

Art Unit: 1756

For: PHOTOMASK BLANK, PHOTOMASK, AND  
METHOD OF MANUFACTURE

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Examiner: S. D. Rosasco

**SUPPLEMENTAL AMENDMENT**

MS Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**INTRODUCTORY COMMENTS**

In further response to the Office Action dated April 16, 2007, please amend the above-identified U.S. patent application as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks/Arguments** begin on page 7 of this paper.